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VII SEMESTER B.TECH. (MECHANICAL & IP ENGINEERING) END SEMESTER MAKE UP EXAMINATIONS, DEC 2016/JAN 2017

SUBJECT: NANOTECHNOLOGY [MME 451]

REVISED CREDIT SYSTEM

(02/01/2017)

Time: 3 Hours MAX. MARKS: 50

Instructions to Candidates:

❖ Answer **ANY FIVE FULL** questions.

1A. 1B. 1C.	Sketch and explain chemical vapor deposition Write a note on future trends in nanotechnology Sketch and explain electric field evaporation of specified atoms	05 03 02
2A.	Sketch and explain the working principle of high precision optical surface sensor	03
2B.	Explain semi-closed and fully closed loop control system used in a numerical control system	03
2C.	Sketch and explain the fabrication process of optical fiber	04
3A.	Explain the working principle of scanning tunneling microscope and explain its two modes of operations	03
3B.	Sketch and explain the working principle of harmonic gear	03
3C.	With respect to nano-lithography explain the following terms (a) positive resist and negative resist (b) thermodynamic resist and kinetic resist	04
4A.	Differentiate between atomic bit processing and atom cluster processing of materials	02
4B.	Explain the modes of operation of transmission electron microscope	03
4C.	With block diagram explain the servo control system for tool positioning of nanometre accuracy	05
5A. 5B.	What are diffraction gratings? How are holographic gratings fabricated? Explain the generation and control of electron beam in a scanning electron	04
	microscope	04
5C.	Sketch and explain elastic hinge	02

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6A.	Sketch and explain the table slide hydraulic guide system	03
6B.	Sketch and explain the manufacturing process of ultra-precision block gauges	04
6C.	Sketch and explain the working of circular path interferometer	03

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